

<b>Notice of References Cited</b>	Application/Control No. 10/585,245		Applicant(s)/Patent Under Reexamination KASAMA ET AL.	
	Examiner MARIANNE L. PADGETT		Art Unit 1715	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2001/0019881	09-2001	Ohmoto et al.	438/584
*	B	US-7,608,162 B2	10-2009	Ohmoto et al.	156/345.44
*	C	US-7,750,297 B1	07-2010	Chow et al.	250/311
	D	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	R					
	S					
	T					

#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Translation of: Rikizo Hatakeyama, "Phenomena be and Application is of Steady-state Discharge Plasma", article published 2002 & previously cited
	V	Translation of Hatakeyama et al., "Characteristics and Applications of fullerene Plasmas", article published 1999 & previously cited.
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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